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[JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **OKANO, Akihiko** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP).

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(74) Agents: **OKABE, Masao** et al.; No. 602, Fuji Bldg., 2-3, Marunouchi 3-chome, Chiyoda-ku, Tokyo 1000005 (JP).

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(71) Applicant (for all designated States except US): **CANON KABUSHIKI KAISHA** [JP/JP]; 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP).

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(72) Inventors; and

(75) Inventors/Applicants (for US only): **KUBOTA, Masahiko** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **SUZUKI, Takumi** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **SATO, Tamaki** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **KANRI, Ryoji** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **HATTA, Maki** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **ASAI, Kazuhiro** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **SHIBA, Shoji** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 1468501 (JP). **ISHIKURA, Hiroe**

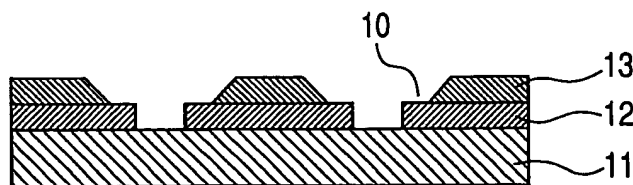
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(54) Title: METHOD FOR MANUFACTURING MINUTE STRUCTURE, METHOD FOR MANUFACTURING LIQUID DISCHARGE HEAD, AND LIQUID DISCHARGE HEAD



ing a desired pattern in the above-mentioned second positive type photosensitive material layer as the upper layer by decomposing reaction without decomposing reaction of the above-mentioned first positive type photosensitive material layer, development using a developing solution, and then, a step of forming a desired pattern in the above-mentioned first positive type photosensitive material layer as the lower layer by decomposing reaction of a predetermined area, and development, whereby a pattern of a convex shape is manufactured in the substrate by executing the above-mentioned steps.

(57) Abstract: A method for manufacturing a minute structure comprises a step of forming a first ionizing radiation decomposing type positive type resist layer to be sensitized by an ionizing radiation of a first wavelength range, a step of forming a second ionizing radiation decomposing type positive type resist layer to be sensitized by an ionizing radiation of a second wavelength range on the first positive type photosensitive material layer, a step of forming

DESCRIPTION

METHOD FOR MANUFACTURING MINUTE STRUCTURE, METHOD FOR
MANUFACTURING LIQUID DISCHARGE HEAD, AND LIQUID
DISCHARGE HEAD

5 TECHNICAL FIELD

The present invention relates to a method for manufacturing a minute structure using a photosensitive resin, and a liquid discharge head for generating recording liquid small droplets used for
10 the ink jet recording system and a method for manufacturing the head. In particular, the present invention relates to a method for manufacturing a head comprising an ink liquid flow path shape, capable of stably discharging minute liquid droplets
15 enabling a high image quality, and furthermore capable of realizing a high speed recording operation. Furthermore, the present invention relates to an ink jet head with the ink discharge properties improved, based on the above-mentioned method for manufacturing
20 an ink jet head.

BACKGROUND ART

A liquid discharge head applied for the ink jet recording system (liquid discharge recording system)
25 for recording by discharging a recording liquid such as an ink in general comprises a liquid flow path, a liquid discharge energy generating part provided in a